

Appl. No. 10/661,439

REMARKS

This Response is submitted in response to the Office Action dated August 9, 2005. The Office Action is a restriction requirement requiring restriction between one of two inventions:

Invention I - claims 1-5, drawn to a plasma enhanced atomic layer deposition apparatus;
and


Invention II - claims 6-13, drawn to a plasma enhanced atomic layer deposition method.

Applicants elect, without traverse, Invention I - claims 1-5, drawn to a plasma enhanced atomic layer deposition apparatus.

Applicants reserve the right to file a divisional application(s), if necessary, to any non-elected claim subject matter.

Respectfully submitted,

BY


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